Amendments to the Specification:

Please replace the paragraph beginning at page 1, line 5, with the following amended paragraph:

The present invention relates to a synthetic silica glass for optical components to be used for ultraviolet light source with a wavelength of 150 to [[200nm]] 190 nm, and a production method therefore. More specifically, the present invention relates to a synthetic silica glass for optical components, such as lens, prism, photomask, window or pellicle, compatible for vacuum-ultraviolet to ultraviolet light from an ArF excimer laser (193 nm), a F_2 laser (157 nm), a low-pressure mercury lamp (185 nm) or a excimer lamp (Xe-Xe: 172 nm).

Please replace the two paragraphs from page 3, line 17 to page 4, line 1, with the following amended paragraphs:

Specifically, the present invention provides a synthetic silica glass for use with light having a wavelength of 150 to [[200]] 190 nm, which has an OH group at a concentration of less than 1 ppm, an oxygen-excess type defect at a concentration of 1×10^{16} defects/cm^3 or less, a hydrogen molecule at a concentration of less than 1×10^{17} molecules/cm^3, and a non-bridging oxygen radical at a concentration of 1×10^{16} radicals/cm^3 or less in the state after the synthetic silica glass is irradiated with light of a xenon excimer lamp having an irradiance of 10 mW/cm^2 and 3 kJ/cm^2.

The present invention further provides a synthetic silica glass for use with light having a wavelength of 150 to [[200]] 190 nm, which has an OH group at a concentration of less than 1 ppm, an oxygen-excess type defect at a concentration of 1×10^{16} defects/cm^3 or less, a hydrogen molecule at a concentration of less than 1×10^{17} molecules/cm^3, and a non-bridging oxygen radical at a concentration of 1×10^{16} radicals/cm^3 or less in the state after the synthetic silica glass is irradiated with light of an F_2 laser by 10^7 pulses at an energy density of 10 mJ/cm^2/pulse.